

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	71	mount-d\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
2	BRS	L2	33	("4944837", "5071485", "5261965", "5314574", "5377705", "5401322", "5417768", "5494526", "5505219", "5509431", "5514220", "5783082", "5868862", "5868862", "5873948", "5881577", "5908510", "5944996", "20020048731", "3968885", "4355937", "4827867", "5013366", "5169408", "5306350", "5368171", "552938", "5976264", "6024801", "6085762", "6090217", "6092538", "6425956", "6602349", "6612317").pn.	US-PGPUB; USPAT

	Type	L #	Hits	Search Text	DBs
3	BRS	L3	3485640	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or process or processing or processing or etch or etching or etched or etchant or strip or stripping or stripped or stripper or decontaminate or decontaminate or decontaminating or decontamination or loosen or loosening or loosened or weaken or weakened or weakening or soak or soaking or soaked or immerse or immersing or immersed or immersion or dip or dipping or dipped or submerge or submerge or submersion or submerged or submerging or rinse or rinsing or rinsed or wash or washing or washed) with (wafer or silicon or semiconductor or substrate or article or surface or object or workpiece or work-piece or electronic or integrated adj2 circuit)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
4	BRS	L4	1026057	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or process or processing or processing or etch or etching or etched or etchant or strip or stripping or stripped or stripper or decontaminate or decontaminate or decontaminating or decontamination or loosen or loosening or loosened or weaken or weakened or weakening or soak or soaking or soaked or immerse or immersing or immersed or immersion or dip or dipping or dipped or submerge or submerge or submersion or submerged or submerging) with (photoresist or resist or polymer or polymeric or organic adj3 material or residue or residual or soil or soiling or soiled or foreign adj5 (matter or material))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
5	BRS	L5	813887	(increase or increasing or increased or change or changing or higher) adj10 (pressure or pressurizing or pressurized) or (pressur\$5) adj10 (cycle or cycled or cycling or difference or differential)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
6	BRS	L6	149424	(multi-pressur\$5 or two-pressur\$5 or two adj4 pressur\$5 or variable adj5 pressur\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
7	BRS	L7	1026057	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or process or processing or processing or etch or etching or etched or etchant or strip or stripping or stripped or stripper or decontaminate or decontaminate or decontaminating or decontamination or loosen or loosening or loosened or weaken or weakened or weakening or soak or soaking or soaked or immerse or immersing or immersed or immersion or dip or dipping or dipped or submerge or submerge or submersion or submerged or submerging) with (photoresist or resist or polymer or polymeric or organic adj3 material or residue or residual or soil or soiling or soiled or foreign adj5 (matter or material))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
8	BRS	L8	813887	(increase or increasing or increased or change or changing or higher) adj10 (pressure or pressurizing or pressurized) or (pressur\$5) adj10 (cycle or cycled or cycling or difference or differential)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
9	BRS	L9	149424	(multi-pressur\$5 or two-pressur\$5 or two adj4 pressur\$5 or variable adj5 pressur\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
10	BRS	L10	3485640	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or process or processing or processing or etch or etching or etched or etchant or strip or stripping or stripped or stripper or decontaminate or decontaminate or decontaminating or decontamination or loosen or loosening or loosened or weaken or weakened or weakening or soak or soaking or soaked or immerse or immersing or immersed or immersion or dip or dipping or dipped or submerge or submerge or submersion or submerged or submerging or rinse or rinsing or rinsed or wash or washing or washed) with (wafer or silicon or semiconductor or substrate or article or surface or object or workpiece or work-piece or electronic or integrated adj2 circuit)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
11	BRS	L11	3909020	L7 or L10	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
12	BRS	L12	885961	L8 or L9	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
13	BRS	L13	18386	L11 with L12	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
14	BRS	L14	394308	("134"/\$ or "510"/\$ or "252"/\$ or "438"/\$).ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
15	BRS	L15	4	l13 and l2	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
16	BRS	L16	58762	(supercritical or super-critical or critical or dense adj3 phase or densified) adj10 (fluid or liquid or gas or carbon adj3 dioxide or "CO2" or "CO.sub.2") or "SCF"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
17	BRS	L17	97	l13 with l16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
18	BRS	L18	256960	(multi-pressur\$5 or two-pressur\$5 or two adj4 pressur\$5 or (varying or varied or changing or vary or variable) adj5 pressur\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
19	BRS	L19	12317	(decompress\$4) with pressur\$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
20	BRS	L20	11	l11 with l19 with l16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
21	BRS	L21	34	l11 same l19 same l16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
22	BRS	L22	1362437	(increase or increasing or increased or change or changing or higher or high or raise or raised or raising) adj10 (pressure or pressurizing or pressurized) or (pressur\$5) adj10 (cycle or cycled or cycling or difference or differential)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
23	BRS	L23	2246307	(decompress\$4 or compress\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
24	BRS	L24	260437	(multi-pressur\$5 or two-pressur\$5 or two adj4 pressur\$5 or multiple adj pressur\$5 or multi adj3 pressur\$5 or (varying or varied or changing or vary or variable) adj5 pressur\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
25	BRS	L25	470790	(decompress\$4 or compress\$4) with pressur\$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
26	BRS	L26	1667864	122 or 124 or 125	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
27	BRS	L27	143399	111 same 126	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
28	BRS	L28	53852	111 with 126	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
29	BRS	L29	360	128 and 116 and 114	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
30	BRS	L30	334	129 not 117	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
31	BRS	L31	410	128 with 116	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
32	BRS	L32	106	131 and 114	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
33	BRS	L33	80	132 not 117	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	71	mount-d\$.in..	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
2	BRS	L2	71	mount-d\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
3	BRS	L4	33	("4944837", "5071485", "5261965", "5314574", "5377705", "5401322", "5417768", "5494526", "5505219", "5509431", "5514220", "5783082", "5868862", "5868862", "5873948", "5881577", "5908510", "5944996", "20020048731", "3968885", "4355937", "4827867", "5013366", "5169408", "5306350", "5368171", "552938", "5976264", "6024801", "6085762", "6090217", "6092538", "6425956", "6602349", "6612317").pn.	US-PGPUB; USPAT

	Type	L #	Hits	Search Text	DBs
4	BRS	L10	1026057	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or process or processing or processing or etch or etching or etched or etchant or strip or stripping or stripped or stripper or decontaminate or decontaminate or decontaminating or decontamination or loosen or loosening or loosened or weaken or weakened or weaking or soak or soaking or soaked or immerse or immersing or immersed or immersion or dip or dipping or dipped or submerge or submerge or submersion or submerged or submerging) with (photoresist or resist or polymer or polymeric or organic adj3 material or residue or residual or soil or soiling or soiled or foreign adj5 (matter or material))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
5	BRS	L11	813887	(increase or increasing or increased or change or changing or higher) adj10 (pressure or pressurizing or pressurized) or (pressur\$5) adj10 (cycle or cycled or cycling or difference or differential)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
6	BRS	L12	149424	(multi-pressur\$5 or two-pressur\$5 or two adj4 pressur\$5 or variable adj5 pressur\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
7	BRS	L13	3485640	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or process or processing or processing or etch or etching or etched or etchant or strip or stripping or stripped or stripper or decontaminate or decontaminate or decontaminating or decontamination or loosen or loosening or loosened or weaken or weakened or weakening or soak or soaking or soaked or immerse or immersing or immersed or immersion or dip or dipping or dipped or submerge or submerge or submersion or submerged or submerging or rinse or rinsing or rinsed or wash or washing or washed) with (wafer or silicon or semiconductor or substrate or article or surface or object or workpiece or work-piece or electronic or integrated adj2 circuit)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
8	BRS	L14	58762	(supercritical or super-critical or critical or dense adj3 phase or densified) adj10 (fluid or liquid or gas or carbon adj3 dioxide or "CO2" or "CO.sub.2") or "SCF"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
9	BRS	L15	12317	(decompress\$4) with pressur\$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
10	BRS	L17	3909020	110 or 113	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
11	BRS	L18	885961	111 or 112	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
12	BRS	L19	18386	117 with 118	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
13	BRS	L21	394308	("134"/\$ or "510"/\$ or "252"/\$ or "438"/\$).ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
14	BRS	L23	26	120 and 121	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
15	BRS	L24	1	120 and 14	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
16	BRS	L3	27	"6602349", "6612317"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
17	BRS	L20	97	119 with 114	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	155478	(dry or drying or dried) with (substrate or workpiece or work-piece or semiconductor or wafer or electronic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
2	BRS	L2	5250	supercritical adj10 ("Tc" or "T.sub.c" or temperature)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
3	BRS	L3	23	l1 with l2	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
4	BRS	L4	25761	invert\$4 adj10 (container or vessel or bath or chamber or reactor or tank)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
5	BRS	L5	216	l1 and l4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
6	BRS	L6	9	l5 and l2	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB